

Aiming at Phenomenal Cleanliness

With the newest Phenom Desktop SEM, VDL ETG is exploring the boundaries of cleanliness

In the high-tech systems industry, the trend is for components, such as vacuum systems, to be cleaner and cleaner. Customers no longer tolerate even the smallest dust particles. However, in order to get rid of them, manufacturers must first be able to see them. With the latest Phenom desktop electron microscope, particles down to one ten-thousandth of a millimeter can be detected. VDL ETG purchased one in the context of research on the cleaning of wafers. In regular production, it has also proven its usefulness.

Methods for cleanliness investigation

"If our clients are going in the direction of increasingly cleaner, then we have to know what we're talking about with them. And knowledge is power," says Geert Jakobs, Managing Director VDL ETG Technology & Development. His company, together with TNO and ASM Europe, is participating in a European research project to develop a new process for cleaning wafers. "We need to gain more understanding of clean manufacturing, and for that purpose, this project is a nice carrier. It is about removing small dust particles, from 100 nanometers (editor: one nanometer is one millionth of a millimeter), from the surfaces of components.

"Our objective in this project is to investigate the production methods we have to use for this. These particles are so small that you can no longer see them with traditional techniques (editor: such as visual inspection using black light). So we searched for a method to detect these particles and to determine where they come from."

Dutch product

Recently VDL ETG purchased the Thermo Scientific™ Phenom Desktop SEM, the tabletop electron microscope from Thermo Fisher Scientific in Eindhoven. The timing is related to the launch earlier this year of the Thermo Scientific™ Phenom ProX Desktop SEM. The new top model attains a resolution (smallest observable detail) of fifteen nanometers at a maximum magnification of 100,000x and features EDX X-ray detection for chemical element analysis.

It is these specifications that won over VDL ETG, says technology manager Luuk Berkelaar. "It was the resolution and magnification that were the most important features for us. In addition, using the elemental analysis, we can determine the chemical composition of the dust particles, so that we can trace their root cause." The deal included the add-on software for the measurement and classification of (dust) particles and for the determination of surface roughness.

